

Title (en)

METHOD OF MANUFACTURING AN X-RAY DIFFRACTION GRATING MICROSTRUCTURE FOR IMAGING APPARATUS

Title (de)

VERFAHREN ZUR HERSTELLUNG EINER MIKROSTRUKTUR EINES RÖNTGEN-DURCHSTRAHLUNGSGITTERS FÜR EIN BILDAUFNAHMEGERÄT

Title (fr)

MÉTHODE DE MANUFACTURE D'UNE MICROSTRUCTURE EN RÉSEAU DE DIFFRACTION DE RAYONS X POUR UN APPAREIL D'IMAGERIE

Publication

**EP 2646602 B1 20160427 (EN)**

Application

**EP 11731520 A 20110610**

Priority

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Abstract (en)

[origin: WO2012073545A1] A microstructure manufacturing method includes forming a first insulating film on an Si substrate, exposing an Si surface by removing a part of the first insulating film, forming a recessed portion by etching the Si substrate from the exposed Si surface, forming a second insulating film on a sidewall and a bottom of the recessed portion, forming an Si exposed surface by removing at least a part of the second insulating film formed on the bottom of the recessed portion, and filling the recessed portion with a metal from the Si exposed surface by electrolytic plating.

IPC 8 full level

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